

# Resource Summary Report

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## Oxford: Instruments P 80 Plasma Etcher

RRID:SCR\_020364

Type: Tool

### Proper Citation

Oxford: Instruments P 80 Plasma Etcher (RRID:SCR\_020364)

### Resource Information

**URL:** <https://plasma.oxinst.com/products/pecvd/plasmapro-800-pecvd#product-information-tabs>

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**Description:** PlasmaPro 800 offers a flexible solution for Plasma Enhanced Chemical Vapour Deposition (PECVD) processes on large wafer batches and 300mm wafers, in a compact footprint, open-loading system. The large wafer platen allows for production scale batch processing and 300mm wafer handling.

**Resource Type:** instrument resource

**Keywords:** Oxford, Plasma Etcher, Instrument Equipment, USEdit

**Availability:** Commercially available

**Resource Name:** Oxford: Instruments P 80 Plasma Etcher

**Resource ID:** SCR\_020364

**Alternate IDs:** Model\_Number\_P80

**Record Creation Time:** 20220129T080349+0000

**Record Last Update:** 20260815T182624+0000

### Ratings and Alerts

No rating or validation information has been found for Oxford: Instruments P 80 Plasma Etcher.

No alerts have been found for Oxford: Instruments P 80 Plasma Etcher.

### Data and Source Information

**Source:** [SciCrunch Registry](#)

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## Usage and Citation Metrics

We have not found any literature mentions for this resource.